

INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>				Docket Number (Optional) CS02-096		Application Number	
				Applicant(s) Lin et al.			
				Filing Date		Group Art Unit	

U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
		US 6,410,191B1		Nistler et al.	/	/	
		US 5,766,829		Cathey, Jr. et al.	/	/	
		US 6,458,495B1		Tsai, et al.	/	/	
		US 6,355,399b1		Sajan et al.	/	/	
		6,482,554		Matsunuma			

FOREIGN PATENT DOCUMENTS								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO

OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>	
	S. Vaidya, Phase-Shifting Photomasks, Semiconductor fabtech, Edition 1, Issued September 1994, S. Vaidya, AT&T Bell Laboratories, Murray Hill, New Jersey, USA, Website: http://www.semiconductorfabtech.com/features/lithography/articles/body1.171.php3 , 5/7/03
	John S. Petersen, et al., Development of a Sub-100nm Integrated Imaging System Using Chromeless Phase-Shifting Imaging with Very High NA KrF Exposure and Off-axis Illumination, found on website; http://www.advlitho.com/content/Papers/SPIE_microlith_02/4691-50_Petersen_Conley_et_al.pdf , May 8, 2003, discusses Chromeless Phase shift mask techniques.

EXAMINER	DATE CONSIDERED 7-6-05
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

